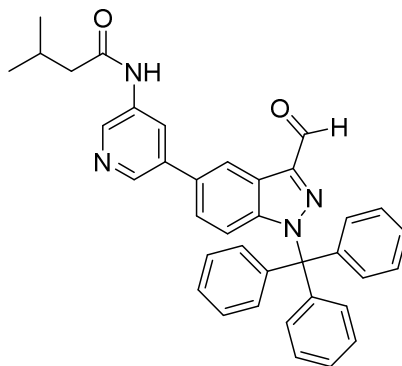
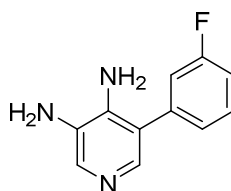




(11)

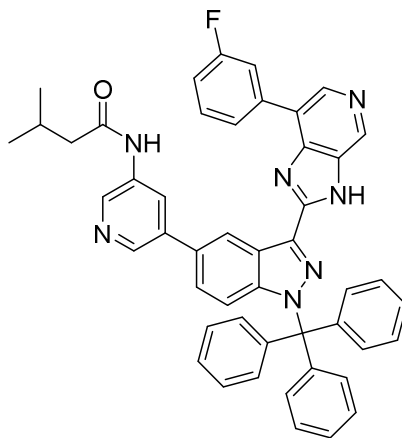
or a salt thereof;

(c) reacting the compound of Formula (11), or the salt thereof, with a compound of Formula (6)



(6)

or a salt thereof, to prepare a compound of Formula (12)



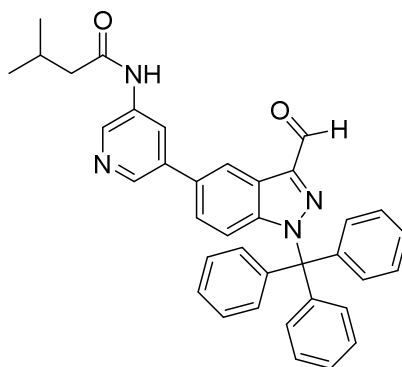
(12)

or a salt thereof; and

(d) deprotecting the compound of Formula (12), or the salt thereof, to prepare the compound of Formula (1), or a salt thereof.

In one aspect, the present disclosure provides a process for preparing a compound of Formula (1)

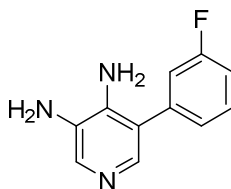
or a salt thereof, with  $\text{Pd(PPh}_3)_4$  and  $\text{K}_3\text{PO}_4$  to prepare a compound of Formula (11)



(11)

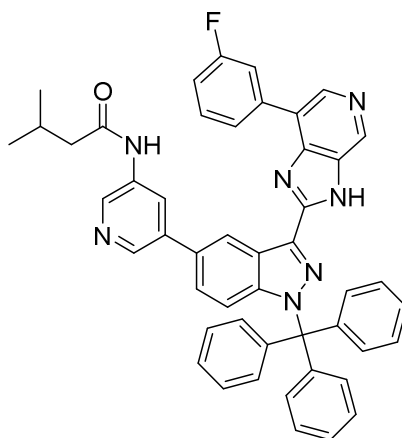
or a salt thereof;

(c) reacting the compound of Formula (11), or the salt thereof, with a compound of Formula (6)



(6)

or a salt thereof, to prepare a compound of Formula (12)



(12)

or a salt thereof; and

(d) deprotecting the compound of Formula (12), or the salt thereof, to prepare the compound of Formula (1), or a salt thereof, wherein deprotecting the compound of Formula (12) to prepare the compound of Formula (1) comprises reacting the compound of Formula (12) with TFA. In some examples, the TFA is neat TFA. In some examples, the ratio

of mass equivalents of TFA to the compound of Formula (12), or a salt thereof, is about 2:1 to about 16:1. In some examples, the ratio of mass equivalents of TFA to the compound of Formula (12), or a salt thereof, is about 7:1 to about 9:1. In some examples, the ratio of mass equivalents of TFA to the compound of Formula (12), or a salt thereof, is about 8:1.

In some examples of the process provided herein, deprotecting the compound of Formula (12), or a salt thereof, is performed at a temperature of about 15°C to about 25°C. In some examples, deprotecting the compound of Formula (12), or a salt thereof, is performed at a temperature of about 20°C.

In some examples of the process provided herein, deprotecting the compound of Formula (12), or a salt thereof, is performed for a time of about 2 hours to about 7 hours. In some examples, deprotecting the compound of Formula (12), or a salt thereof, is performed for a time of about 3 hours to about 7 hours. In some examples, deprotecting the compound of Formula (12), or a salt thereof, is performed for a time of about 2 hours to about 4 hours. In some examples, deprotecting the compound of Formula (12), or a salt thereof, is performed for a time of about 5 hours. In some examples, deprotecting the compound of Formula (12), or a salt thereof, is performed for a time of about 3 hours.

In some examples of the process provided herein, deprotecting the compound of Formula (12), or a salt thereof, comprises forming a first mixture; and adding water to the first mixture at a temperature of about 0°C to about 10°C to form a second mixture. In some examples, water is added at a temperature of about 5°C to form the second mixture. In some examples, the process comprises reslurrying the second mixture for a time of about 0.5 hours to about 1 hour. In some examples, the process comprises reslurrying the second mixture for a time of about 0.75 hours. In some examples, the process comprises reslurrying the second mixture at a temperature of about 0°C to about 10°C. In some examples, the process comprises reslurrying the second mixture at a temperature of about 5°C.

In some examples, the process further comprises filtering the second mixture to provide a filtrate. In some examples, the process further comprises adding water to the filtrate at a temperature of about 0°C to about 10°C to form a third mixture. In some examples, water is added to the filtrate at a temperature of about 5°C to form the third mixture. In some examples, the process comprises reslurrying the third mixture at a temperature of about 5°C to about 15°C. In some examples, the process comprises reslurrying the third mixture at a temperature of about 10°C. In some examples, the process comprises reslurrying the third mixture for a time of about 1 hour to about 2 hours. In some

examples, the process comprises reslurrying the third mixture for a time of about 1.5 hours. In some examples, the process further comprises filtering the third mixture to provide a first residual solid.

In some examples of the process provided herein, the process further comprises adding ethanol to the first residual solid to form a fourth mixture. In some examples, the process comprises reslurrying the fourth mixture at a temperature of about 25°C to about 35°C. In some examples, the process comprises reslurrying the fourth mixture at a temperature of about 30°C. In some examples, the process comprises reslurrying the fourth mixture for a time of about 2 hours to about 4 hours. In some examples, the process comprises reslurrying the fourth mixture for a time of about 3 hours. In some examples, the process comprises filtering the fourth mixture to provide a second residual solid.

In some examples of the process provided herein, the process comprises adding water to the second residual solid to form a fifth mixture. In some examples, the process comprises reslurrying the fifth mixture at a temperature of about 20°C to about 30°C. In some examples, the process comprises reslurrying the fifth mixture at a temperature of about 25°C. In some examples, the process comprises reslurrying the fifth mixture for a time of about 0.5 hour to about 1.5 hours. In some examples, the process comprises reslurrying the fifth mixture for a time of about 1 hour.

In some examples of the process provided herein, the process comprises adding a base to the fifth mixture to form a sixth mixture. In some examples, the base is selected from the group consisting of: lithium carbonate, sodium carbonate, potassium carbonate, cesium carbonate, sodium hydrogen carbonate, potassium hydrogen carbonate, sodium sulfate, potassium sulfate, cesium sulfate, lithium phosphate, sodium phosphate, potassium phosphate, and cesium phosphate. In some examples, the base is sodium carbonate. In some examples, the process comprises reslurrying the sixth mixture at a temperature of about 20°C to about 30°C. In some examples, the process comprises reslurrying the sixth mixture at a temperature of about 25°C. In some examples, the process comprises reslurrying the sixth mixture for a time of about 5 hours to about 7 hours. In some examples, the process comprises reslurrying the sixth mixture for a time of about 6 hours. In some examples, the process further comprises filtering the sixth mixture to provide a third residual solid.

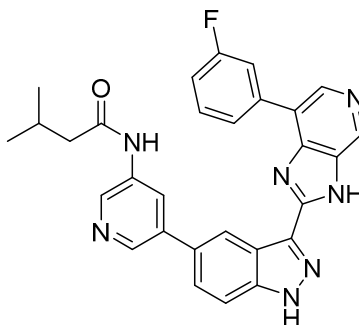
In some examples of the process provided herein, the process further comprises adding water to the third residual solid to form a seventh mixture. In some examples, the process comprises reslurrying the seventh mixture at a temperature of about 20°C to about 30°C. In some examples, the process comprises reslurrying the seventh mixture at a

temperature of about 25°C. In some examples, the process comprises reslurrying the seventh mixture for a time of about 5 hours to about 8 hours. In some examples, the process comprises reslurrying the seventh mixture for a time of about 6.5 hours. In some examples, the process further comprises filtering the seventh mixture to provide a fourth residual solid.

In some examples of the process provided herein, the process further comprises (a) adding water to the fourth residual solid to provide an eighth mixture; (b) reslurrying the eighth mixture; and (c) filtering the eighth mixture to provide a fifth residual solid. In some examples, steps (a)-(c) are performed an additional one or more times.

In some examples of the process provided herein, the process further comprises adding isopropanol to the fifth residual solid to form a ninth mixture. In some examples, the process comprises reslurrying the ninth mixture at a temperature of about 20°C to about 30°C. In some examples, the process comprises reslurrying the ninth mixture at a temperature of about 25°C. In some examples, the process comprises reslurrying the ninth mixture for a time of about 1 hour to about 3 hours. In some examples, the process comprises reslurrying the ninth mixture for a time of about 2 hours. In some examples, the process further comprises filtering the ninth mixture to provide a sixth residual solid.

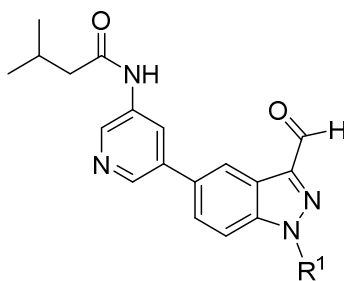
Also provided herein is a process for preparing a compound of Formula (1)



(1)

or a salt thereof, the process comprising:

(a) reacting the compound of Formula (5)



(5)

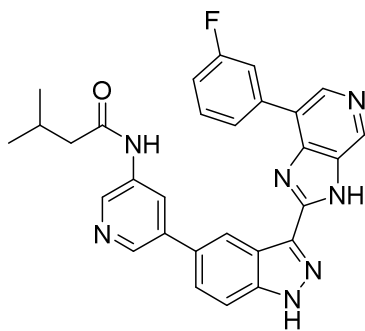
the process comprising: (a) preparing the compound of Formula (1) according to any one of the processes provided herein; and (b) converting the compound of Formula (1) to the polymorph form. In some examples, step (b) comprises reslurrying the compound of Formula (1) or a composition comprising the compound of Formula (1) in a solvent or mixture of solvents to generate the polymorph form. In some examples, reslurrying is performed at room temperature. In some examples, reslurrying is performed at a temperature of about 50°C. In some examples, reslurrying is performed at a temperature of about 30°C to about 35°C. In some examples, reslurrying is performed for a time of about 10 hours to about 80 hours. In some examples, reslurrying is performed for a time of about 58 hours to about 80 hours.

In some examples, the process further comprises a filtering step to provide the polymorph form as a residual solid.

In some examples, the reslurrying comprises a solvent or mixture of solvents selected from methanol, water, or a mixture thereof.

In some examples, the polymorph form of the compound of Formula (1) is a non-stoichiometric hydrate of polymorph Form 1 having between 1% and about 20% by weight water.

Also provided is a process for preparing a polymorph form of a compound of Formula (1)



(1),

the process comprising converting the compound of Formula (1) to the polymorph form. In some examples, the process comprises reslurrying the compound of Formula (1) or a composition comprising the compound of Formula (1) in a solvent or mixture of solvents to generate the polymorph form. In some examples, the reslurrying is performed at room temperature. In some examples, the reslurrying is performed at a temperature of about 50°C. In some examples, the reslurrying is performed at a temperature of about 30°C to about 35°C. In some examples, the reslurrying is performed for a time of about 10 hours

to about 80 hours. In some examples, the reslurrying is performed for a time of about 58 hours to about 80 hours. In some examples, the process further comprises a filtering step to provide the polymorph form as a residual solid.

In some examples, the reslurrying comprises a solvent or mixture of solvents selected from methanol, water, or a mixture thereof.

In some examples, the polymorph form of the compound of Formula (1) is a non-stoichiometric hydrate of polymorph Form 1 having between 1% and about 20% by weight water.

### DESCRIPTION OF DRAWINGS

**FIGS. 1A-1D** are scans of polymorph Form 1 of the compound of Formula (I). **FIG. 1A** is an x-ray powder diffraction scan of fully dried Form 1. **FIG. 1B** is a differential scanning calorimetry scan of Form 1. **FIG. 1C** is a thermal gravimetric analysis scan of Form 1. **FIG. 1D** is a dynamic vapor sorption scan of Form 1.

**FIGS. 2A-2H** are scans of polymorph Forms 2, 2\*, and 2\*\* of the compound of Formula (I). **FIG. 2A** is an x-ray powder diffraction scan of fully dried Form 2. **FIG. 2B** is a differential scanning calorimetry scan of Form 2. **FIG. 2C** is a thermal gravimetric analysis scan of Form 2. **FIG. 2D** is an x-ray powder diffraction scan of fully dried Form 2\*. **FIG. 2E** is a differential scanning calorimetry scan of Form 2\*. **FIG. 2F** is a thermal gravimetric analysis scan of Form 2\*. **FIG. 2G** is an x-ray powder diffraction scan of Form 2\*\*. **FIG. 2H** is a differential scanning calorimetry scan of Form 2\*\*.

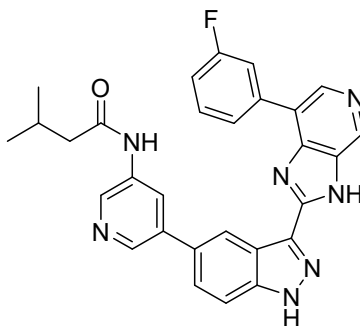
**FIGS. 3A-3C** are scans of polymorph Form 3 of the compound of Formula (I). **FIG. 3A** is an x-ray powder diffraction scan of fully dried Form 3. **FIG. 3B** is a differential scanning calorimetry scan of Form 3. **FIG. 3C** is a thermal gravimetric analysis scan of Form 3.

**FIGS. 4A-4I** are scans of polymorph Forms 4, 4\*, and 4\*\* of the compound of Formula (I). **FIG. 4A** is an x-ray powder diffraction scan of fully dried Form 4. **FIG. 4B** is a differential scanning calorimetry scan of Form 4. **FIG. 4C** is a thermal gravimetric analysis scan of Form 4. **FIG. 4D** is an x-ray powder diffraction scan of fully dried Form 4\*. **FIG. 4E** is a differential scanning calorimetry scan of Form 4\*. **FIG. 4F** is a thermal gravimetric analysis scan of Form 4\*. **FIG. 4G** is an x-ray powder diffraction scan of Form 4\*\*. **FIG. 4H** is a differential scanning calorimetry scan of Form 4\*\*. **FIG. 4I** is a thermal gravimetric analysis scan of Form 4\*\*.

**FIGS. 5A-5D** are scans of polymorph Forms 5 and 5\* of the compound of Formula (I). **FIG. 5A** is an x-ray powder diffraction scan of fully dried Form 5. **FIG. 5B** is a differential

**WHAT IS CLAIMED IS:**

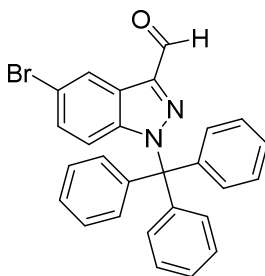
1. A process for preparing a compound of Formula (1)



(1)

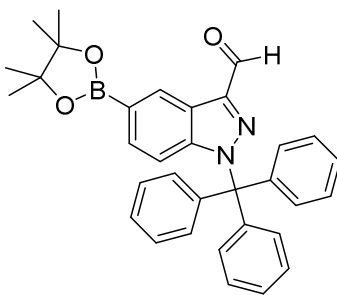
or a salt thereof, the process comprising:

- (a) reacting a compound of Formula (8)



(8)

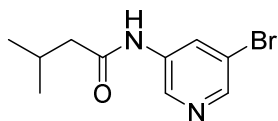
or a salt thereof, with bis(pinacolato)diboron and Pd(dppf)Cl<sub>2</sub> to produce a compound of Formula (9)



(9)

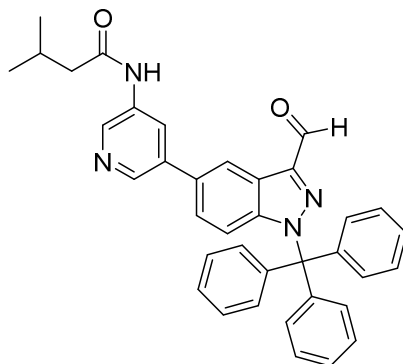
or a salt thereof;

- (b) reacting the compound of Formula (9), or the salt thereof, with a compound of Formula (10)



(10)

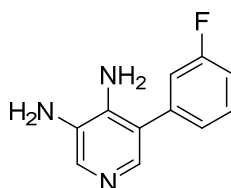
or a salt thereof,  $\text{Pd}(\text{PPh}_3)_4$  and  $\text{K}_3\text{PO}_4$  to prepare a compound of Formula (11)



(11)

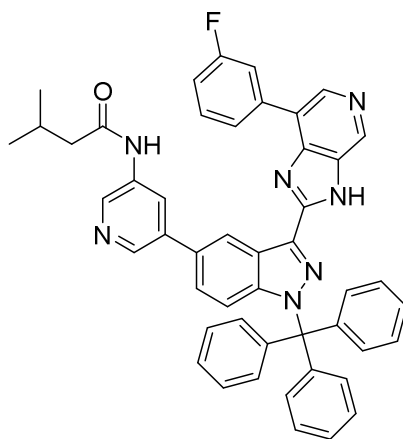
or a salt thereof,

(c) reacting the compound of Formula (11), or the salt thereof, with a compound of Formula (6)



(6)

or a salt thereof, to prepare a compound of Formula (12)



(12)

or a salt thereof; and

(d) deprotecting the compound of Formula (12), or the salt thereof, to prepare the compound of Formula (1), or a salt thereof, wherein deprotecting the compound of Formula (12) to prepare the compound of Formula (1) comprises reacting the compound of Formula (12) with TFA.

2. The process of claim 1, wherein the ratio of molar equivalents of Pd(dppf)Cl<sub>2</sub> to the compound of Formula (8), or a salt thereof, is about 0.01:1 to about 0.1:1.

3. The process of claim 2, wherein the ratio of molar equivalents of Pd(dppf)Cl<sub>2</sub> to the compound of Formula (8), or a salt thereof, is about 0.03:1.

4. The process of claim 1, wherein the ratio of molar equivalents of Pd(PPh<sub>3</sub>)<sub>4</sub> to the compound of Formula (9), or a salt thereof, is about 0.01:1 to about 0.1:1.

5. The process of claim 4, wherein the ratio of molar equivalents of Pd(PPh<sub>3</sub>)<sub>4</sub> to the compound of Formula (9), or a salt thereof, is about 0.03:1.

6. The process of claim 5, wherein the ratio of K<sub>3</sub>PO<sub>4</sub> to the compound of Formula (10), or a salt thereof, is about 3:1.

7. The process of claim 6, wherein reacting the compound of Formula (9), or a salt thereof, with the compound of Formula (10), or a salt thereof, to prepare the compound of Formula (11), or a salt thereof, is performed in the presence of 1,4-dioxane.

8. The process of claim 7, wherein reacting the compound of Formula (9), or a salt thereof, with the compound of Formula (10), or a salt thereof, to prepare the compound of Formula (11), or a salt thereof, is performed under an inert atmosphere.

9. The process of claim 8, wherein reacting the compound of Formula (9), or a salt thereof, with the compound of Formula (10), or a salt thereof, to prepare the compound of Formula (11), or a salt thereof, is performed under an N<sub>2</sub> atmosphere.

10. The process of claim 9, wherein reacting the compound of Formula (9), or a salt thereof, with the compound of Formula (10), or a salt thereof, to prepare the compound of Formula (11), or a salt thereof, is performed at a temperature of about 80°C to about 100°C for a time of about 1 hour to about 5 hours.

11. The process of claim 10, wherein reacting the compound of Formula (9), or a salt thereof, with the compound of Formula (10), or a salt thereof, to prepare the compound of Formula (11), or a salt thereof, is performed at a temperature of about 85°C to about 95°C for a time of about 2 hours to about 3 hours.

12. The process of claim 1, further comprising precipitating the compound of Formula (11) in water prior to reacting the compound of Formula (11), or a salt thereof, with

the compound of Formula (6), or a salt thereof, to prepare the compound of Formula (12), or a salt thereof.

**13.** The process of claim 1, further comprising preparing a salt of the compound of Formula (11) prior to reacting the compound of Formula (11), or the salt thereof, with the compound of Formula (6), or a salt thereof, to prepare the compound of Formula (12), or a salt thereof.

**14.** The process of claim 13, further comprising preparing an oxalate salt of the compound of Formula (11) prior to reacting the compound of Formula (11), or the salt thereof, with the compound of Formula (6), or a salt thereof, to prepare the compound of Formula (12), or a salt thereof.

**15.** The process of claim 1, further comprising preparing a free base form of the compound of Formula (11) prior to reacting the compound of Formula (11), or the salt thereof, with the compound of Formula (6), or a salt thereof, to prepare the compound of Formula (12), or a salt thereof.

**16.** The process of claim 12, further comprising precipitating the compound of Formula (11), or a salt thereof, in a non-polar organic solvent prior to reacting the compound of Formula (11), or a salt thereof, with the compound of Formula (6), or a salt thereof, to prepare the compound of Formula (12), or a salt thereof.

**17.** The process of claim 16, further comprising precipitating the compound of Formula (11), or a salt thereof, in n-heptane prior to reacting the compound of Formula (11), or a salt thereof, with the compound of Formula (6), or a salt thereof, to prepare the compound of Formula (12), or a salt thereof.

**18.** The process of claim 1, further comprising one or more of:

- (a) precipitating the compound of Formula (11) in water;
- (b) preparing a salt of the compound of Formula (11) from the precipitated compound of Formula (11);
- (c) preparing a free base form of the compound of Formula (11) from the salt of the compound of Formula (11); and
- (d) precipitating the free base form of the compound of Formula (11) in a nonpolar organic solvent, prior to reacting the compound of Formula (11), or the salt thereof, with the compound of Formula (6), or a salt thereof, to prepare the compound of Formula (12), or a salt thereof.

**19.** The process of claim 18, further comprising one or more of:

- (a) precipitating the compound of Formula (11) in water;

(b) preparing an oxalate salt of the compound of Formula (11) from the precipitated compound of Formula (11);

(c) preparing a free base form of the compound of Formula (11) from the salt of the compound of Formula (11); and

(d) precipitating the free base form of the compound of Formula (11) in *n*-heptane, prior to reacting the compound of Formula (11), or the salt thereof, with the compound of Formula (6), or a salt thereof, to prepare the compound of Formula (12), or a salt thereof.

**20.** The process of claim 1, wherein reacting the compound of Formula (11), or a salt thereof, with the compound of Formula (6), or a salt thereof, to prepare the compound of Formula (12), or a salt thereof, is performed in the presence of  $\text{Na}_2\text{SO}_3$ .

**21.** The process of claim 20, wherein the  $\text{Na}_2\text{SO}_3$  is ground  $\text{Na}_2\text{SO}_3$ .

**22.** The process of claim 20, wherein reacting the compound of Formula (11), or a salt thereof, with the compound of Formula (6), or a salt thereof, to prepare the compound of Formula (12), or a salt thereof, is performed in the presence of *N*-methyl-2-pyrrolidone.

**23.** The process of claim 22, wherein reacting the compound of Formula (11), or a salt thereof, with the compound of Formula (6), or a salt thereof, to prepare the compound of Formula (12), or a salt thereof, is performed under an inert atmosphere.

**24.** The process of claim 23, wherein reacting the compound of Formula (11), or a salt thereof, with the compound of Formula (6), or a salt thereof, to prepare the compound of Formula (12), or a salt thereof, is performed under an  $\text{N}_2$  atmosphere.

**25.** The process of claim 24, wherein reacting the compound of Formula (11), or a salt thereof, with the compound of Formula (6), or a salt thereof, to prepare the compound of Formula (12), or a salt thereof, is performed at a temperature of about 100°C to about 120°C for a time of about 5 hours to about 10 hours.

**26.** The process of claim 25, wherein reacting the compound of Formula (11), or a salt thereof, with the compound of Formula (6), or a salt thereof, to prepare the compound of Formula (12), or a salt thereof, is performed at a temperature of about 110°C to about 115°C for a time of about 7 hours to about 9 hours.

**27.** The process of claim 1, further comprising preparing a salt of the compound of Formula (12) prior to deprotecting the compound of Formula (12), or the salt thereof, to prepare the compound of Formula (1), or a salt thereof.

**28.** The process of claim 27, further comprising preparing an oxalate salt of the compound of Formula (12) prior to deprotecting the compound of Formula (12), or the salt thereof, to prepare the compound of Formula (1), or a salt thereof.

**29.** The process of claim 1, further comprising preparing a free base form of the compound of Formula (12) prior to deprotecting the compound of Formula (12), or a salt thereof, to prepare the compound of Formula (1), or a salt thereof.

**30.** The process of claim 1, further comprising precipitating the compound of Formula (12), or a salt thereof, in a nonpolar organic solvent prior to deprotecting the compound of Formula (12), or a salt thereof, to prepare the compound of Formula (1), or a salt thereof.

**31.** The process of claim 30, further comprising precipitating the compound of Formula (12), or a salt thereof, in n-heptane prior to deprotecting the compound of Formula (12), or a salt thereof, to prepare the compound of Formula (1), or a salt thereof.

**32.** The process of claim 6, further comprising one or more of:  
(a) preparing a salt of the compound of Formula (12);  
(b) preparing a free base form of the compound of Formula (12) from the salt of the compound of Formula (12); and  
(c) precipitating the free base form compound of Formula (12) in a nonpolar organic solvent, prior to deprotecting the compound of Formula (12), or a salt thereof, to prepare the compound of Formula (1), or a salt thereof.

**33.** The process of claim 32, further comprising one or more of:  
(a) preparing an oxalate salt of the compound of Formula (12);  
(b) preparing a free base form of the compound of Formula (12) from the oxalate salt of the compound of Formula (12); and  
(c) precipitating the free base form compound of Formula (12) in n-heptane, prior to deprotecting the compound of Formula (12), or a salt thereof, to prepare the compound of Formula (1), or a salt thereof.

**34.** The process of claim 1, wherein the TFA is neat TFA.

**35.** The process of claim 34, wherein the ratio of mass equivalents of TFA to the compound of Formula (12), or a salt thereof, is about 2:1 to about 16:1.

**36.** The process of claim 35, wherein the ratio of mass equivalents of TFA to the compound of Formula (12), or a salt thereof, is about 8:1.

**37.** The process of claim 35, wherein deprotecting the compound of Formula (12), or a salt thereof, is performed at a temperature of about 15°C to about 25°C.

**38.** The process of claim 37, wherein deprotecting the compound of Formula (12), or a salt thereof, is performed for a time of about 2 hours to about 7 hours.

**39.** The process of claim 38, wherein deprotecting the compound of Formula (12), or a salt thereof, is performed for a time of about 5 hours.

**40.** The process of claim 38, wherein deprotecting the compound of Formula (12), or a salt thereof, is performed for a time of about 3 hours.

**41.** The process of claim 1, wherein deprotecting the compound of Formula (12), or a salt thereof, comprises:

forming a first mixture;

adding water to the first mixture at a temperature of about 0°C to about 10°C to form a second mixture;

reslurrying the second mixture for a time of about 0.5 hours to about 1 hour at a temperature of about 0°C to about 10°C;

filtering the second mixture to provide a filtrate;

adding water to the filtrate at a temperature of about 0°C to about 10°C to form a third mixture.

reslurrying the third mixture at a temperature of about 5°C to about 15°C for a time of about 1 hour to about 2 hours; and

filtering the third mixture to provide a first residual solid.

**42.** The process of claim 41, further comprising:

adding ethanol to the first residual solid to form a fourth mixture;

reslurrying the fourth mixture at a temperature of about 25°C to about 35°C for a time of about 2 hours to about 4 hours;

filtering the fourth mixture to provide a second residual solid;

adding water to the second residual solid to form a fifth mixture;

reslurrying the fifth mixture at a temperature of about 20°C to about 30°C for a time of about 0.5 hour to about 1.5 hours;

adding a base to the fifth mixture to form a sixth mixture;

reslurrying the sixth mixture at a temperature of about 20°C to about 30°C for a time of about 5 hours to about 7 hours;

filtering the sixth mixture to provide a third residual solid;

adding water to the third residual solid to form a seventh mixture;

reslurrying the seventh mixture at a temperature of about 20°C to about 30°C for a time of about 5 hours to about 8 hours;

filtering the seventh mixture to provide a fourth residual solid;  
adding water to the fourth residual solid to provide an eighth mixture;  
reslurrying the eighth mixture;  
filtering the eighth mixture to provide a fifth residual solid;  
adding isopropanol to the fifth residual solid to form a ninth mixture;  
reslurrying the ninth mixture at a temperature of about 20°C to about 30°C for  
a time of about 1 hour to about 3 hours; and  
filtering the ninth mixture to provide a sixth residual solid.

**43.** The process of claim 1, further comprising:

- (a) reslurrying the compound of Formula (1) in a solvent to generate the polymorph, wherein the solvent is selected from acetonitrile, n-butyl acetate, n-butanol, dichloromethane (DCM), heptane, isopropyl alcohol (IPAc), methanol, methyl acetate (MA), methyl *tert*-butyl ether (MtBE), methyl isobutyl ketone (MIBK), toluene, water, or a mixture thereof; wherein reslurrying is performed at a temperature of about room temperature to about 50°C; wherein reslurrying is performed for a time of about 10 hours to about 80 hours; and
- (b) filtering at a relative humidity (RH) above 30% to provide the polymorph as a residual solid; wherein the polymorph has an XRPD pattern with at least peaks at  $2\theta$  positions of  $6.4\pm 0.2$ ,  $11.0\pm 0.2$ , and  $18.4\pm 0.2$ ; and wherein the polymorph exhibits an exotherm at around 278°C.

**44.** The process of claim 43, wherein reslurrying is performed at room temperature.

**45.** The process of claim 43, wherein reslurrying is performed at a temperature of about 50°C.

**46.** The process of claim 41, wherein reslurrying is performed at a temperature of about 30°C to about 35°C.

**47.** The process of claim 41, wherein reslurrying is performed for a time of about 58 hours to about 80 hours.

**48.** The process of claim 47, wherein the solvent is selected from methanol, water, or a mixture thereof.

**49.** The process of claim 48, wherein the solvent is 90% methanol/water.

**50.** The process of claim 48, wherein the solvent is methanol; and wherein reslurrying is performed at a temperature of about 50°C.

**51.** The process of claim 43, wherein the polymorph has an XRPD pattern with at least peaks at  $2\theta$  positions  $6.4\pm0.2$ ,  $9.2\pm0.2$ ,  $11.0\pm0.2$ ,  $15.6\pm0.2$ ,  $16.1\pm0.2$ ,  $18.4\pm0.2$ ,  $19.7\pm0.2$ ,  $20.8\pm0.2$ ,  $24.4\pm0.2$ , and  $25.2\pm0.2$ .

**52.** The process of claim 43, wherein the polymorph exhibits an endotherm between about 50-100°C as measured by DSC.

**53.** The process of claim 43, wherein the polymorph has a melting point of around 363°C.

**54.** The process of claim 47, wherein the solvent is acetonitrile/water; and wherein reslurrying is performed at a temperature of about 50°C.

**55.** The process of claim 47, wherein the solvent is isopropyl alcohol/water; and wherein reslurrying is performed at a temperature of about 50°C.

**56.** The process of claim 47, wherein the solvent is methyl *tert*-butyl ether/water; and wherein reslurrying is performed at a temperature of about 50°C.

**57.** The process of claim 47, wherein the solvent is methyl isobutyl ketone/water; and wherein reslurrying is performed at a temperature of about 50°C.

**58.** The process of claim 48, wherein the solvent is water; and wherein reslurrying is performed at a temperature selected from about room temperature or about 50°C.

**59.** The process of claim 47, wherein the solvent is toluene/water; and wherein reslurrying is performed at a temperature selected from about room temperature or about 50°C.

**60.** The process of claim 47, wherein the solvent is methyl acetate/water; and wherein reslurrying is performed at a temperature of about room temperature.

**61.** The process of claim 47, wherein the solvent is n-butyl acetate/water; and wherein reslurrying is performed at a temperature selected from about room temperature or about 50°C

**62.** The process of claim 47, wherein the solvent is heptane; and wherein reslurrying is performed at a temperature of about 50°C

**63.** The process of claim 47, wherein the solvent is n-heptane/water; and wherein reslurrying is performed at a temperature selected from about room temperature or about 50°C.

**64.** The process of claim 47, wherein the solvent is n-butanol/water; and wherein reslurrying is performed at a temperature selected from about room temperature or about 50°C.

**65.** The process of claim 47, wherein the solvent is dichloromethane; and wherein reslurrying is performed at a temperature of about 50°C.

**66.** The process of claim 47, wherein the solvent is dichloromethane/water; and wherein reslurrying is performed at a temperature selected from about room temperature or about 50°C.

**67.** The process of claim 1, further comprising:

- (a) reslurrying the compound of Formula (1) in a solvent to generate the polymorph; wherein the solvent is selected from acetonitrile, ethyl acetate (EA), isopropyl alcohol (IPAc), methanol, methyl acetate (MA), methyl *tert*-butyl ether (MtBE), methyl isobutyl ketone (MIBK), water, or a mixture thereof; wherein reslurrying is performed at a temperature selected from about room temperature or about 50°C; wherein reslurrying is performed for a time of about 10 hours to about 80 hours; and
- (b) filtering at a relative humidity (RH) above 30% to provide the polymorph as a residual solid; wherein the polymorph has an XRPD pattern with at least peaks at  $^{\circ}2\theta$  positions of  $6.4\pm0.2$ ,  $11.0\pm0.2$ , and  $18.4\pm0.2$ ; wherein Form 12 exhibits an exotherm at around 283°C.

**68.** The process of claim 67, wherein the solvent is acetonitrile/water; and wherein reslurrying is performed at a temperature of about room temperature.

**69.** The process of claim 67, wherein the solvent is isopropyl alcohol/water; and wherein reslurrying is performed at a temperature of about room temperature.

**70.** The process of claim 67, wherein the solvent is methyl *tert*-butyl ether/water; and wherein reslurrying is performed at a temperature of about room temperature.

**71.** The process of claim 67, wherein the solvent is methyl isobutyl ketone/water; and wherein reslurrying is performed at a temperature of about room temperature.

**72.** The process of claim 67, wherein the solvent is ethyl acetate/water; and wherein reslurrying is performed at a temperature of about room temperature.

**73.** The process of claim 67, wherein the solvent is methanol/water; and wherein reslurrying is performed at a temperature of about room temperature.

**74.** The process of claim 67, wherein the solvent is methyl acetate/water; and wherein reslurrying is performed at a temperature of about 50°C.

**75.** The process of claim 67, wherein the polymorph has an XRPD pattern with at least peaks at  $^{\circ}2\theta$  positions  $6.4\pm0.2$ ,  $9.2\pm0.2$ ,  $11.0\pm0.2$ ,  $15.6\pm0.2$ ,  $16.1\pm0.2$ ,  $18.4\pm0.2$ ,  $19.7\pm0.2$ ,  $20.8\pm0.2$ ,  $24.4\pm0.2$ , and  $25.2\pm0.2$ .

**76.** The process of claim 67, wherein the polymorph exhibits an endotherm between about 50-100°C as measured by DSC.

**77.** The process of claim 67, wherein the polymorph has a melting point of around 364°C.